

Sustainable air plasma regeneration of screen-printed gold electrodes with enhanced electroactive surface area and biosensing performance

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List of Abbreviation

Abbreviation	Full Form
AFM	Atomic force microscopy
C_{dl}	Double layer capacitance
CPE	Constant phase element
CV	Cyclic voltammetry
ssDNA	Single strand deoxyribonucleic acid
EIS	Electrochemical impedance spectroscopy
E-Polish	Electropolish
MCH	Mercaptohexanol
OCP	Open circuit potential
POC	Point of care
R_{ct}	Charge transfer resistance
RF	Radio frequency
RSD	Relative standard deviation
R_u	Uncompensated resistance
SAM	Self assemble monolayer
SEM	Scanning electron microscope
SPE	Screen printed electrode
TBA	Thrombin binding aptamer
TBS	Tris buffer saline
WCA	Water contact angle
XPS	X-ray photoelectron spectroscopy
Z_w	Warburg impedance

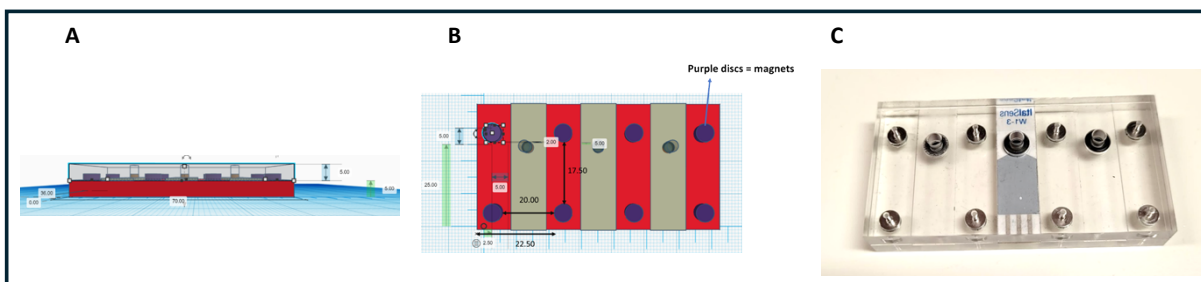


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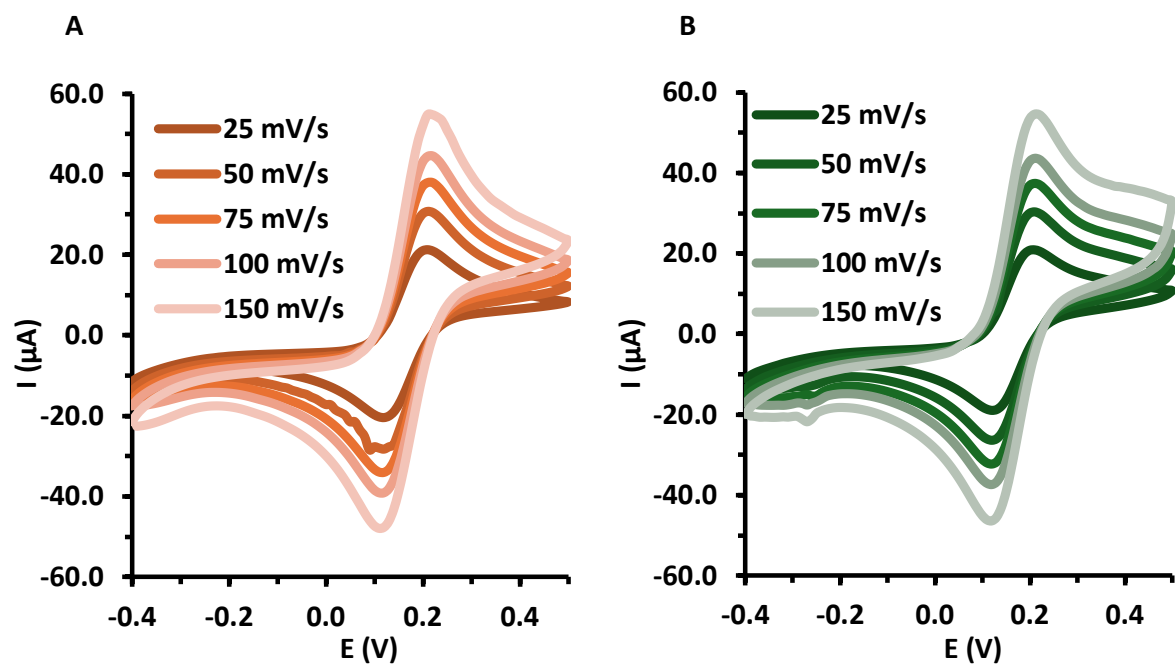


Fig. S2. Cyclic voltammograms of A) E-polished and B) plasma cleaned/E-polished gold SPE in the measurement buffer solution at scan rates 25–150 mV/s vs pseudo-Ag/AgCl paste.

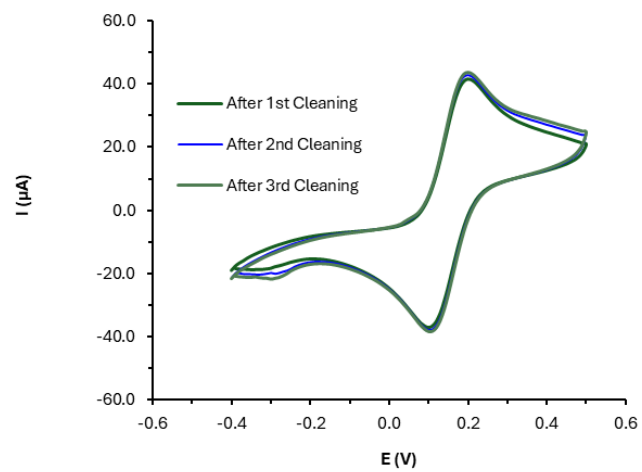


Fig. S3. Cyclic voltammograms of a gold SPE in TBS 1X and ferro/ferricyanide 2 mM after each cycle of plasma cleaning.

Table. S1. Electrochemical characteristics of a new (untreated), used, and plasma cleaned gold SPE showcasing the improved electrochemical performance and higher surface area via air plasma cleaning.

Parameters	New	Used	Plasma cleaned
I_{peak} (μA)	49.5	6.8	77.4
ΔE_{peak} (V)	0.18	0.47	0.11
S_{true} (cm^2)	0.21	0.15	0.26
R_{ct} (Ω)	1.1	6.1	0.43
C_{dl} (μF)	1.3	0.64	3.2

Table. S2. Comparison of plasma treatment parameters of this work with previously published studies.

System	Plasma Power	Sample Size	Pressure	Time	Application	Advantage	Limitation
RF discharge air plasma, (this work)	30 W ~10 mW/cm ³	Substrate 15.2 cm x 16.5 cm	0.7 Torr	10 min	Recycling, pre-treatment	Cleans multiple electrodes simultaneously, simple operation, at least 3 recycles	Initial high cost
arc-discharge air-plasma generator ⁹	12.9 W	Localized 0.11 cm ²	atmospheric	15 s per electrode	Pre-treatment	No pump is required, rapid treatment	Require manual assembly
Plasma pen ³	NA	Localized	atmospheric	2 min	Pre-treatment	No pump is required	Dependence on operator skills
radiofrequency argon flow discharge ¹⁰	50-300 W	Substrate 10 cm diameter	0.67-6.65Pa	2-15 min	Pre-treatment	Improved electron transfer kinetics	High power consumption

Table. S3. Fixed parameter values for the Randel-Sevcik and Warburg impedance equations for diffusion calculations.

Parameter	Value
A (cm ²)	0.21
C (mol/cm ³)	2×10 ⁻⁶
n	1
R (J/mol.K)	8.314
F C/mol	96,485
Constant	0.446
T (K)	295

Table. S4. Warburg Impedance coefficient (σ) derived from faradaic EIS tests for electrodes treated under two conditions.

Parameter	E-polished	Plasma cleaned/E-polished
σ ($\Omega \cdot s^{-1/2}$)	1071	1461

Table. S5. The oxidation peak currents for electrodes treated under two conditions were measured at stepwise increasing scan rates during cyclic voltammetry tests.

$v^{1/2}$ (V/s)	E- polished	Plasma cleaned/E-polished
	ip (μA)	ip (μA)
0.025	23.839	22.039
0.050	33.619	29.553
0.075	41.035	37.823
0.100	47.518	43.696
0.150	58.814	53.784

Table. S6. Peak binding energy (BE) comparison form XPS analysis of gold SPE in this work with previously published studies.

Element	Peak BE (This work)	Peak BE (Reference)
Au4f _{7/2}	Used: 84.02 eV	Chromium and gold on glass substrate: 83.95 eV ⁴ Gold nanoparticles supported on oxides: 84.00 eV ⁵ Spin-orbit coupling: 3.7 eV ⁵
	New: 84.49 eV	
	Plasma cleaned: 84.18 eV	
	Spin-orbit coupling: 3.7 eV	
C1s	Used: 285.04 eV	sp ² C=C (284 eV), sp ³ C-C (285 eV), and C-OH (286.88 eV) ⁶
	New: 284.89 eV	
	Plasma cleaned: 285.08 eV	
N1s	Used: 400.34 eV	Common organic nitrogen species: 399- 400.6 eV ⁸ C-NH2: 400 eV ^{7, 8}
	New: 400.29 eV	
	Plasma cleaned: 400.08 eV	
O1s	Used: 532.14 eV	Common organic oxygen species 532.0 - 533.7 eV ⁶
	New: 532.29 eV	
	Plasma cleaned: 532.58 eV	